IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

PATENT APPLICATION

riventor(s):	Scheiberlich								
Appin. No.:	09	827,350							
	Series Code ↑	Serial No. ↑	OIP						
Filed: April 6, 2001									
			APR 2 3 2003						
Sir:									
Series Code ↑ Serial No. ↑ Series Code ↑ Serial No. ↑ Idea: April 6, 2001 Ion. Commissioner of Patents Vashington, D.C. 20231									

Group Art U Examiner:

Atty. Dkt.

2851

Hung Nguyen 279263

P-0177.010-US

Client Ref

M# Appln. Title: Lithographic apparatus, device manufacturing method, and device

manufactured thereby

April 23, 2003 Date:

This is a reply/amendment/letter in the above-identified application and includes the herewith attachment of same date and subject which is incorporated hereinto by reference and the signature below is treated as the signature to the attachment in absence of a signature thereto.

FEE REQUIREMENTS FOR CLAIMS AS AMENDED

1. Small Entity claim A. ⋈ NOT made See Required Separate Paper	Claims	Highest nu	mber	Present Extra	Large/Small Entity	Additional	Fee Code
B. Withdrawn C. made herewith (Pat-256)	remaining after amendment	previously paid for				Fee	Lg/Sm
D. made previously	amenument						Lyroin
2. Total Effective Claims	17	**minus	20	0	x \$18/\$9 =	+ \$0	103/203
3. Independent Claims	4	***minus	3	1	x \$84/\$42 =	+ \$84	102/202
4. If amendment enters proper multi							
time (leave <u>blank</u> if this is a <u>reissue</u>	+ \$280/\$140 =	+ \$0	104/204				
5. Original due Date: February 2		<u> </u>	Mind M				
6. Petition is hereby made to exter		78 899	115/215				
date to cover the date this response	+ \$410	•	116/216				
requisite fee is attached		1,	117/217 118/218				
			128/228				
		120/220					
7. Enter any previous extension fee	- \$0		(dålik uje				
8.	Extension Fee	+ \$410	Je sije sij <u>t</u>				
9. If Terminal Disclaimer attached,	+ \$110/\$55	+ \$0	148/248				
10. If IDS attached requires Official	+ \$180	+ \$0	126				
or if Rule 97(d) Request	+ \$180	1 \$0	126				
11. After-Final Request Fee per rule	+ \$750/370	+ \$0	146/246				
12. No. of additional inventions for e	x \$750/375 ea	+ \$0	149/249				
13. Request for Continued Examina	+ \$750/375	+ \$0	1179/1279				
14. Petition fee for	+ \$0						
15.	\$494						
16. *If the entry in this space is less than entr	PLEASE CHARGE						
17. **If the "Highest number previously paid	OUR DEP. ACCT						
18. ***If the "Highest number previously pa							

04/24/2003 HVUONG1 00000044 033975 09827350

(Our Order No. 81468

62 FC:1252 STATEMENT The Commissioner is hereby authorized to charge any fee specifically authorized hereafter, or any missing or insufficient fee(s) filed, or asserted to be filed, or which should have been filed herewith or concerning any paper filed hereafter, and which may be required under Rules 16-18 (missing or insufficiencies only) now or hereafter relative to this application and the resulting Official Document under Rule 20, or credit any overpayment, to our Accounting/Order Nos. shown above, for which purpose a duplicate copy of this sheet is attached.

This CHARGE STATEMENT does not authorize charge of the issue fee until/unless an issue fee transmittal sheet is filed.

Query: Is appeal deadline now? If so, file Notice of Appeals separately

Pillsbury Winthrop LLP Intellectual Property Group

By Atty: Robert C. Perez

39,328 Reg. No.

McLean, VA 22102 Tel: (703) 905-2000

Sig:

Fax: (703) 905-2500 Tel: (703) 905-2159

Atty/Sec: RP/mll

P.O. Box 10500

NOTE: File this cover sheet in duplicate with PTO receipt (PAT-103A) and attachments

IN THE LINKED STATES PATENT AND TRADEMARK OFFICE Confirmation No.: 2993

In re PATENT APPLICATION OF

SCHEIBERLICH et al.

Appln. No.: 09/827,350

Filed: April 6, 2001

Title: LITHOGRAPHIC APPARATUS, DEVICE MANUFACTURING METHOD, AND

Group Art Unit: 2851

Examiner: H. NGUYEN

DEVICE MANUFACTURED THEREBY

April 23, 2003

AMENDMENT

Hon. Commissioner of Patents Washington, D.C. 20231

Sir: In response to the Office Action dated November 29, 2002, please amend the aboveidentified application as follows:

IN THE SPECIFICATION:

Page 9, delete the whole paragraph starting in line 6 and replace it with the following new paragraph:

The beam PB subsequently intercepts the mask MA, which is held on a mask table MT. Having traversed the mask MA, the beam PB passes through the lens PL, which focuses the beam PB onto a target portion C of the substrate W. With the aid of the second positioning means (and interferometric measuring means IF), the substrate table WT can be moved accurately, e.g., so as to position different target portions C in the path of the beam PB using wafer alignment marks P1, P2. Similarly, the first positioning means can be used to accurately position the mask MA using mask alignment marks M1, M2 with respect to the path of the beam PB, e.g., after mechanical retrieval of the mask MA from a mask library, or during a scan. In general, movement of the object tables MT, WT will be realized with the